CLEANING METHOD AND CLEANING SYSTEM FOR SEMICONDUCTOR STORAGE CONTAINER

ABSTRACT

A cleaning method, cleaning unit and cleaning system for a semiconductor storage container. The cleaning method comprises the following steps: S21, placing a container in a second cleaning chamber; S22, vacuumizing the second cleaning chamber until the vacuum degree in the second cleaning chamber is lower than a first preset pressure value; S23, filling the second cleaning chamber with gas at a first volumetric flow rate; and S24, filling the second cleaning chamber with gas at a second volumetric flow rate, wherein the first volumetric flow rate is less than the second volumetric flow rate, and the maximum pressure value in the second cleaning chamber during S23 is less than the maximum pressure value in the second cleaning chamber during S24.

Fig 17.